

EV Group announces multi-functional micro- and nanoimprint solution 'EVG7300' - January 20, 2022

EVG introduced the EVG®7300 automated SmartNIL® nanoimprint and wafer-level optics system. "The latest introduction to our family of nanoimprint solutions, the EVG7300, combines our SmartNIL full-field imprint technology with lens molding and lens stacking in a state-of-the-art system with the most precise alignment and process parameter control on the market—providing our customers with unprecedented flexibility for their industry research and production needs." stated Thomas Glinsner, corporate technology director at EV Group. The EVG7300 is a highly flexible platform that offers three different process modes (lens molding, lens stacking and SmartNIL nanoimprint) and support for substrate sizes ranging from 150-mm to 300-mm wafers.

